The M4L™ is our most popular full featured plasma surface modification system designed for laboratory and production use.

The M4L is ideal for:

- Plasma surface modification
- Plasma cleaning of organic surfaces
- Plasma cleaning of metallic surfaces
- Bond strength enhancement
- Plasma etch applications
- Plasma ashing applications
- Increased or decreased wettability
- Any other plasma system application

The entire bench top system fits in one cabinet, except for the vacuum pump. Never before has a professional plasma etch system been this loaded with features and priced this affordably!

Technical Details

- Controller: Windows® O/S based touch screen interface offering fully automatic control. Multi-step recipes, real time graphic display, multi-level password access, data logging, and real time SPC monitoring of all plasma parameters is provided.

- Chamber: 9" X 13" X 20" Aluminum, with high-conductance KF 40 port and isolation valve. Optional throttle valve available.

- Electrode options include 3-shelf, 5-shelf, and cage electrodes.

- RF Generator: 300 or 600 watt 13.56 MHz air cooled with automatic impedance matching network.

- Display: Color 10.4 inch touch screen for control and monitoring of process
parameters, automatic recipes, or manual plasma treatments.

- Two user specified gases, with 500 sccm MFCs standard, Optional 3rd gas channel available.

- Power Requirements: 120-240 volts, 1Ø, 50/60 Hz 30 amps maximum, changeable in the field.

- CE Certified